ASSIGNEE: INTEL CORPORATION

02207/12663

Serial No. 10/074,003

AMENDMENTS

IN THE CLAIMS

10. (Currently Amended) A space transformer comprising:

a silicon medium; and

a predetermined contact pattern comprising electrically conductive material

disposed in an inner region of the substrate and defining electrical contact zones located

to provide double-sided electrical contacts for the space transformer, the contacts

comprising land grid array side contacts having dimensions and spacing in the order of

mils, and semiconductor side contacts having dimensions and spacing in the order of

microns, said land grid array side contacts having dimensions and spacing less than said

semiconductor side contacts.

11. (Original) The space transformer according to claim 10, wherein the silicon

medium comprises a first silicon layer and a second silicon layer, the contact pattern

being disposed between the first silicon layer and the second silicon layer.

12. (Previously amended) The space transformer according to claim 11, wherein the

second silicon layer defines at least one via therein, at least some of the electrically

conductive material being located in the at least one via.

2

ASSIGNEE: INTEL CORPORATION

02207/12663

Serial No. 10/074,003

13. (Original) The space transformer according to claim 11, further comprising an

adhesion promoter disposed between the electrically conductive material and the first

silicon layer.

14. (Currently Amended) A space transformer comprising:

a first silicon layer defining a plurality of vias therein;

a predetermined contact pattern comprising copper on the first silicon

layer, at least some of the copper being disposed in the plurality of vias for defining

electrical contact zones in the plurality of vias to provide double-sided electrical contacts

for the space transformer, the contacts comprising land grid array side contacts having

dimensions and spacing in the order of mils, and semiconductor side contacts having

dimensions and spacing in the order of microns; and

a second silicon layer disposed on the contact pattern, the contact pattern

being disposed in an inner region located between the first silicon layer and the second

silicon layer, the contacts comprising land grid array side contacts and semiconductor

side contacts, said land grid array side contacts having dimensions and spacing less than

said semiconductor side contacts.

15. (Original) The space transformer according to claim 14, further comprising a

layer of adhesion promoter disposed between the electrically conductive material and the

first silicon layer.

16. (Currently Amended) A space transformer comprising:

3

ASSIGNEE: INTEL CORPORATION

02207/12663

Serial No. 10/074,003

a first silicon layer;

a second silicon layer mounted to the first silicon layer; and

means disposed in an inner region located between the first silicon layer

and the second silicon layer for providing double-sided electrical contacts for the space

transformer, the contacts comprising land grid array side contacts having dimensions and

spacing in the order of mils, and semiconductor side contacts having dimensions and

spacing in the order of microns, said land grid array side contacts having dimensions and

spacing less than said semiconductor side contacts.

17. (Original) The space transformer according to claim 16, wherein the means for

providing comprises a contact pattern comprising electrically conductive material.

4